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By:

Linda E. Hastings
LINDA E. HASTINGS

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Attorney Docket No.:NEKW14.868

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EVA
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NE

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor: KAICHIRO NAKANO, ET AL.

Serial No.: 09/036,219

Filed: March 6, 1998

Title: **CHEMICALLY AMPLIFIED RESIST LARGE IN
TRANSPARENCY AND SENSITIVITY TO EXPOSURE
LIGHT LESS THAN 248 NANOMETER WAVELENGTH
AND PROCESS OF FORMING MASK**

Examiner: J. Chu

Group Art Unit: 1752

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February 27, 2001

Assistant Commissioner for Patents
BOX NON-FEE AMENDMENT
Washington, D.C. 20231

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RESPONSE TO OFFICE ACTION

S I R :

In response to the Office Action mailed on November 29, 2000, the period for responding thereto having been set to expire on February 28, 2001, please amend the above-captioned application as follows:

E